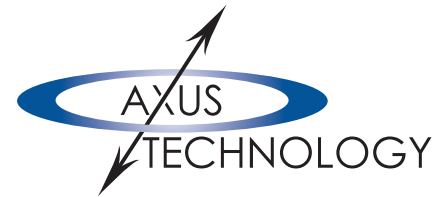
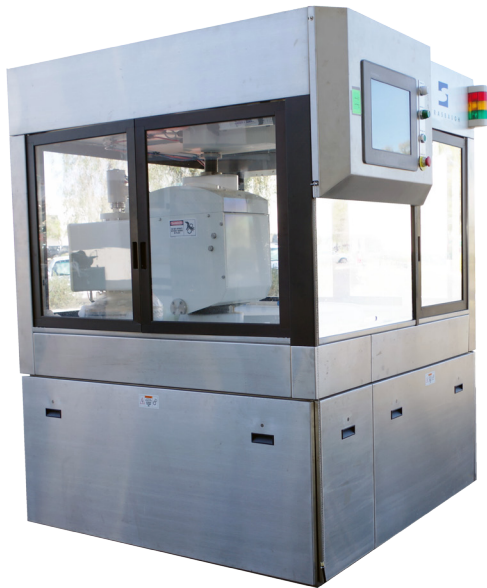


# Strasbaugh 6EG CMP System

## For 300mm CMP of Thin Films



Your source for leading-edge surface processing solutions



The remanufactured Model 6EG CMP Planarizer by Axus Technology, provides an economical way for limited production fabs, and research groups to polish thin films on 300mm substrates, achieving polishing results comparable to those possible on multi-million-dollar production level CMP tools. The "Titan," advanced membrane wafer carrier upgrade delivers significant process and productivity improvements.

Semi-Automatic Load/Unload, coupled with automatic polishing cycle sequencing programmable through the PC controller via the color touch-screen GUI, gives the process engineer the features and benefits of high-throughput, large footprint, expensive production level CMP tools. The Model 6EG from Axus Technology is the affordable solution, providing the benefits of state-of-the-art CMP in a small footprint polishing tool, and at an attractive price.

## FEATURES

- Closed-loop table drive motors and spindle drive motors help ensure consistent process results.
- The programmable pad conditioning system provides in-situ and/or ex-situ programmable selective pad conditioning for:
  - » Consistent removal rates
  - » Optimized within-wafer-non-uniformity (WIWNU)
  - » 23 zones of selectable conditioning parameters such as traversing time, dwell time, down force, and rpm.
- Robust design and quality components help to minimize maintenance requirements thus driving down the total Cost-of-Ownership.
- The relatively small footprint works well in smaller lab spaces and in the typical R&D environment

## Options

### Titan Carrier Upgrade

- Improves Edge Exclusion to 3mm
- Increases removal rate by up to 2X or more, over first gen OEM carriers
- Results in improved WIWNU and WTWNU
- Improves throughput and reduces process cost